

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1533		SERIAL NO. 09/754,926	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Kie Y. Ahn et al.			
				FILING DATE January 4, 2001		GROUP 2813	
U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
AA							
FOREIGN PATENT DOCUMENTS							
	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
AB							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AC		<del>"High Quality Ta<sub>2</sub>O<sub>5</sub> Gate Dielectrics with T<sub>ox</sub> &lt; 10 Å" H.F. Luan, S.J. Lee, C.H. Lee, S.C. Song, Y.L. Mao, Y. Senzaki, D. Roberts, and D.L. Kwong, IEDM, pp. 141-144, 1999.</del>				
EK	AD		Article: "High-K Dielectrics for Giga-Scale CMOS and Non-Volatile Memory Technology"; L. Manchanda, G. Alers, and J.P. Han, March 15, 2000.				
EK	AE		Article: "Application of Al <sub>2</sub> O <sub>3</sub> Grown by Atomic Layer Deposition to DRAM and FeRAM; C.T. Kim, C. Lim, K.M. Kim, M.S. Kim, H.K. Jang, Y.S. Yu and J.S. Roh, pg. 316, March 13, 2000				
EK	AF		Article: Beam Solid Interactions: Fundamentals and Applications; Materials Research Society Symposium Proceedings; Volume 279; pp. 825-830; Symposium held November 30-December 4, 1992.				
	AG		<del>"Effect of Plasma Activation on the Phase Transformations of Aluminum Oxide"; O. Zywicki, G. Hoetzel, Surface &amp; Coatings Technology 76-77, 1995; pp. 754-762</del>				
	AH		<del>Article: "Tunability of Intrinsic Stress in SiO<sub>2</sub> Dielectric Films Formed By Molecular Beam Deposition"; Naresh Chand, R.R. Kofa, J.W. Osobach, and W.T. Tsang, pp. 195-200, Volume 356, 1995.</del>				
EK	AI		"Optical Thin Films IV: New Developments"; James D. Rancourt; SPIE - The International Society for Optical Engineering; Volume 2262; pp. 14-21; July 1994.				
	AJ						
EXAMINER <i>Erik Kuhn</i>			DATE CONSIDERED <i>5/8/02</i>				
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